

17  
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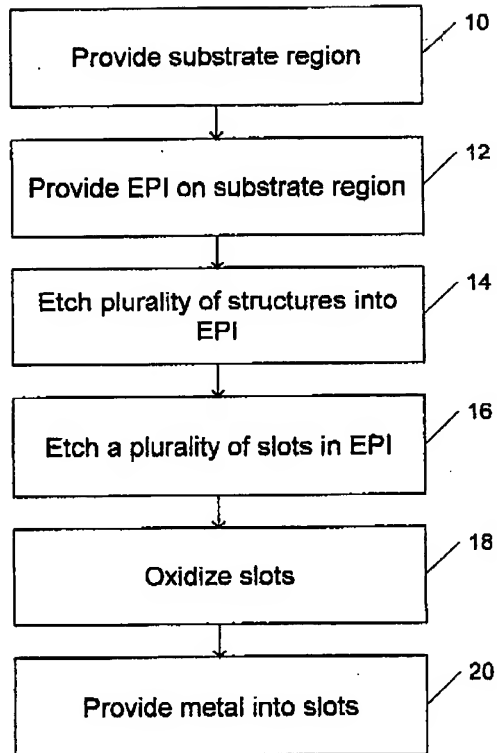


Fig. 1

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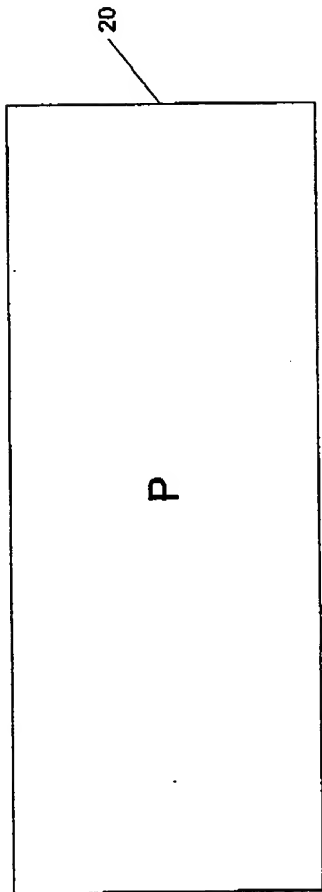


Fig. 2a

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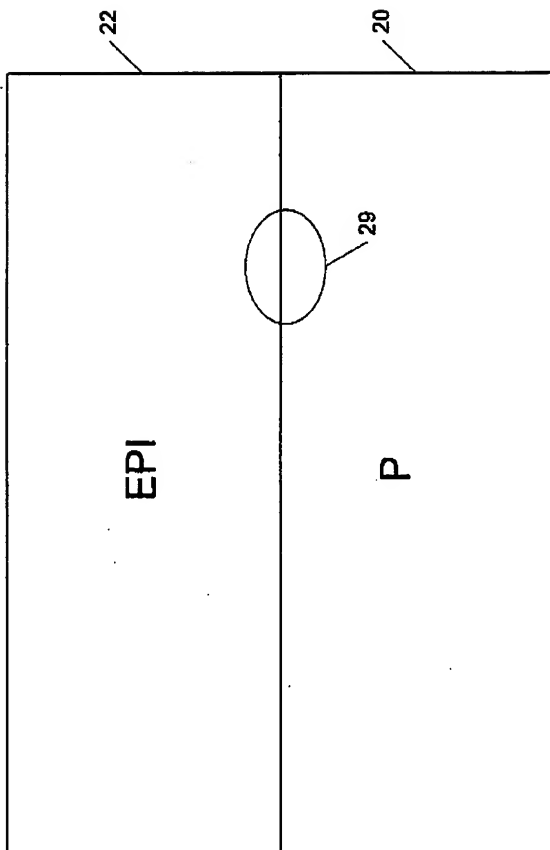


Fig. 2b

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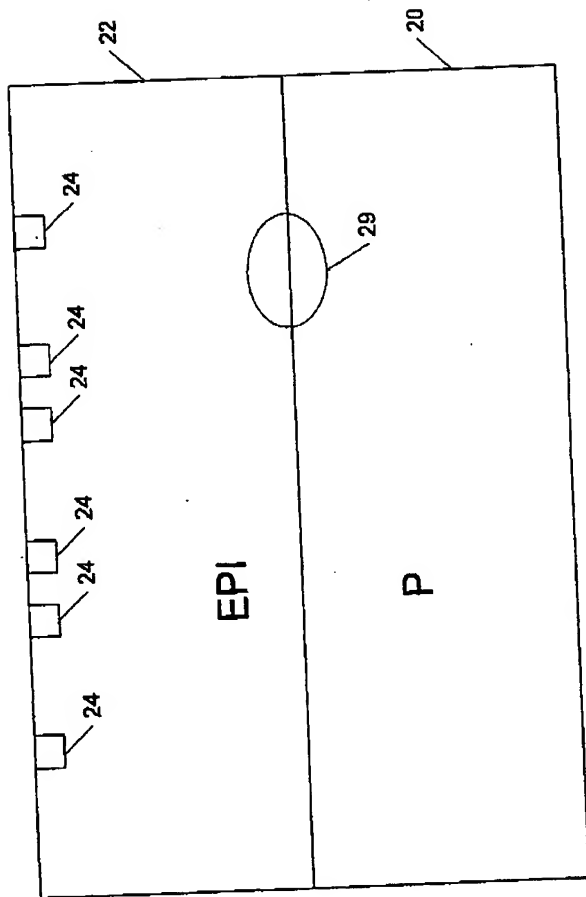


Fig. 2c

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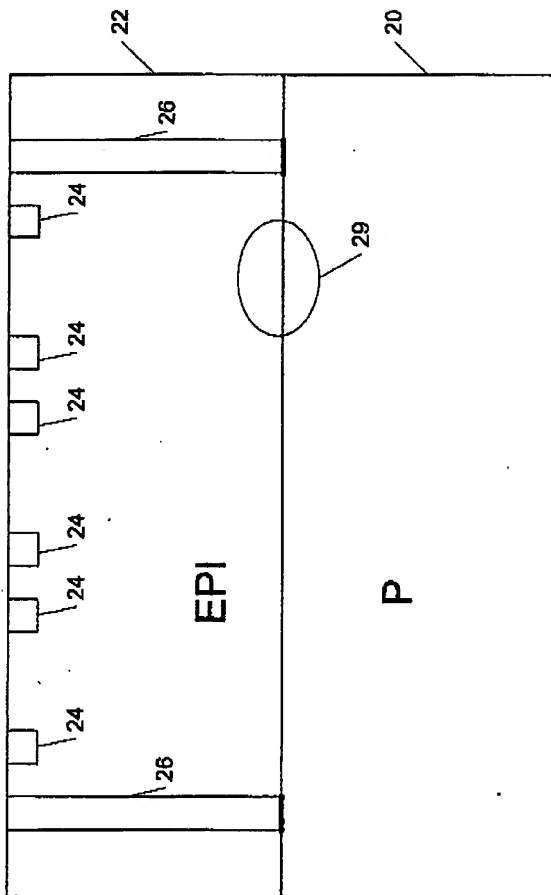


Fig. 2d

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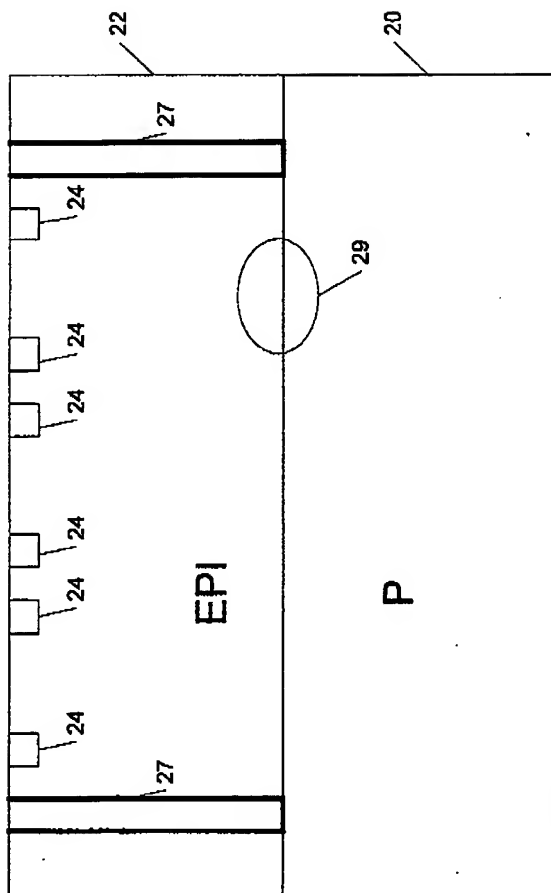


Fig. 2e

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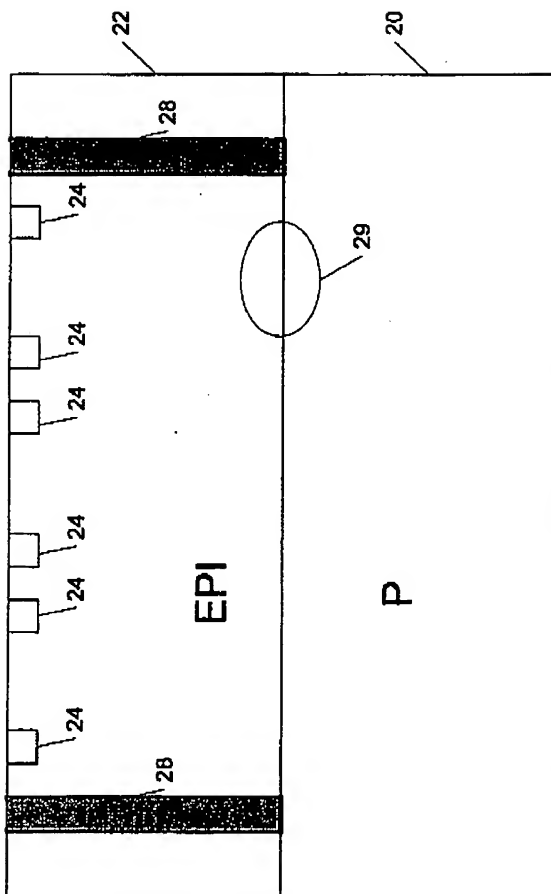


Fig. 2f

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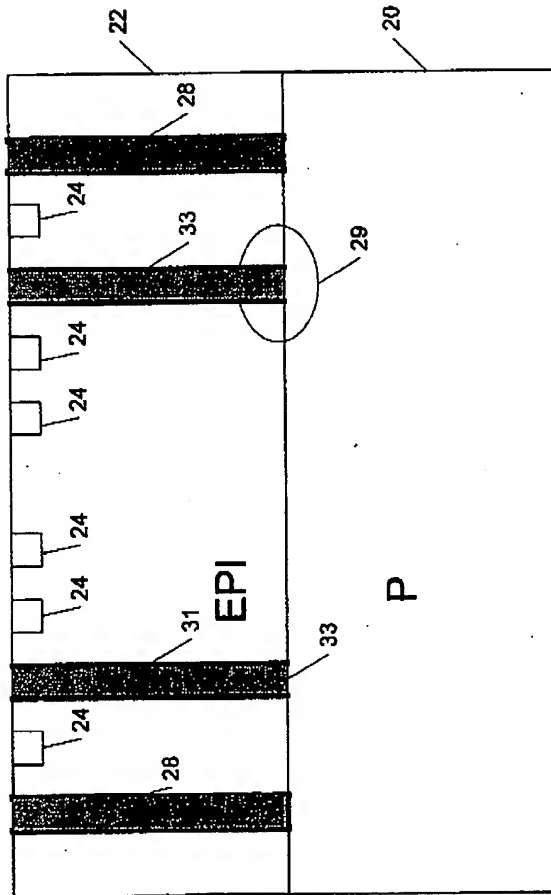


Fig. 2g

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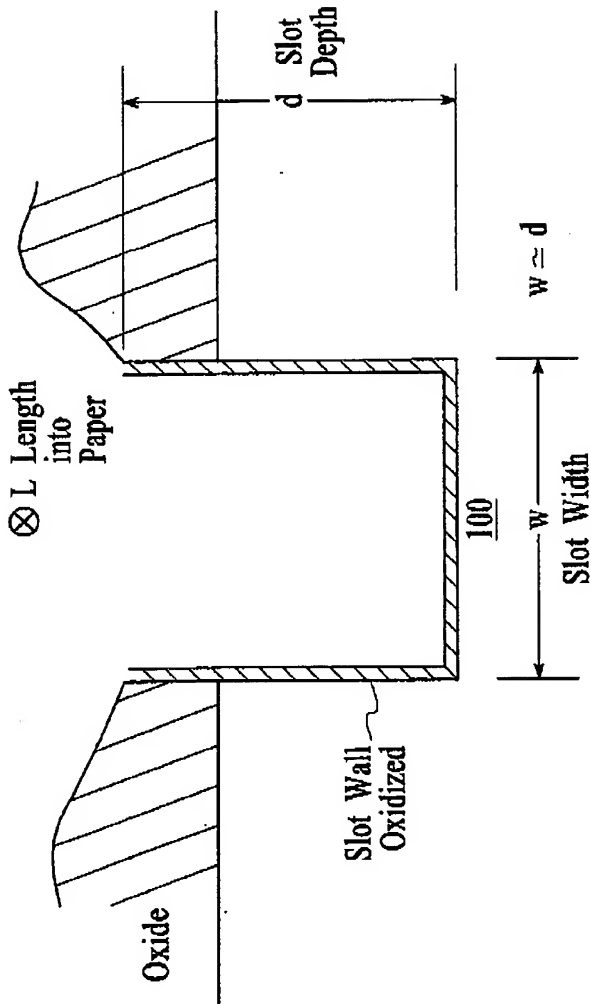


FIG. 3

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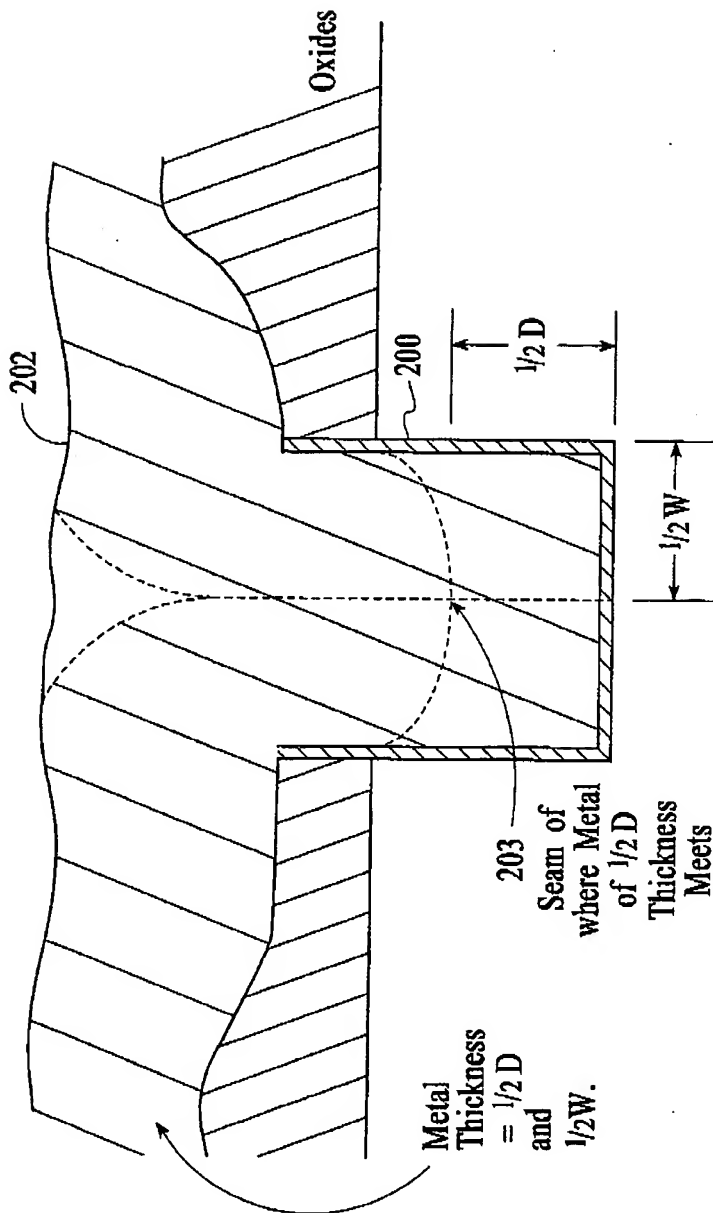
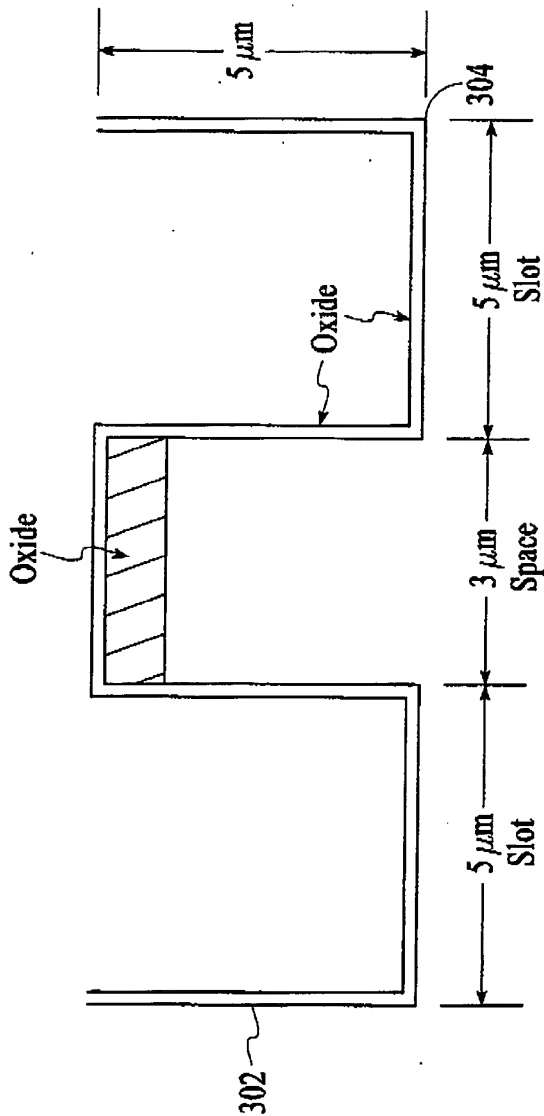


FIG. 4

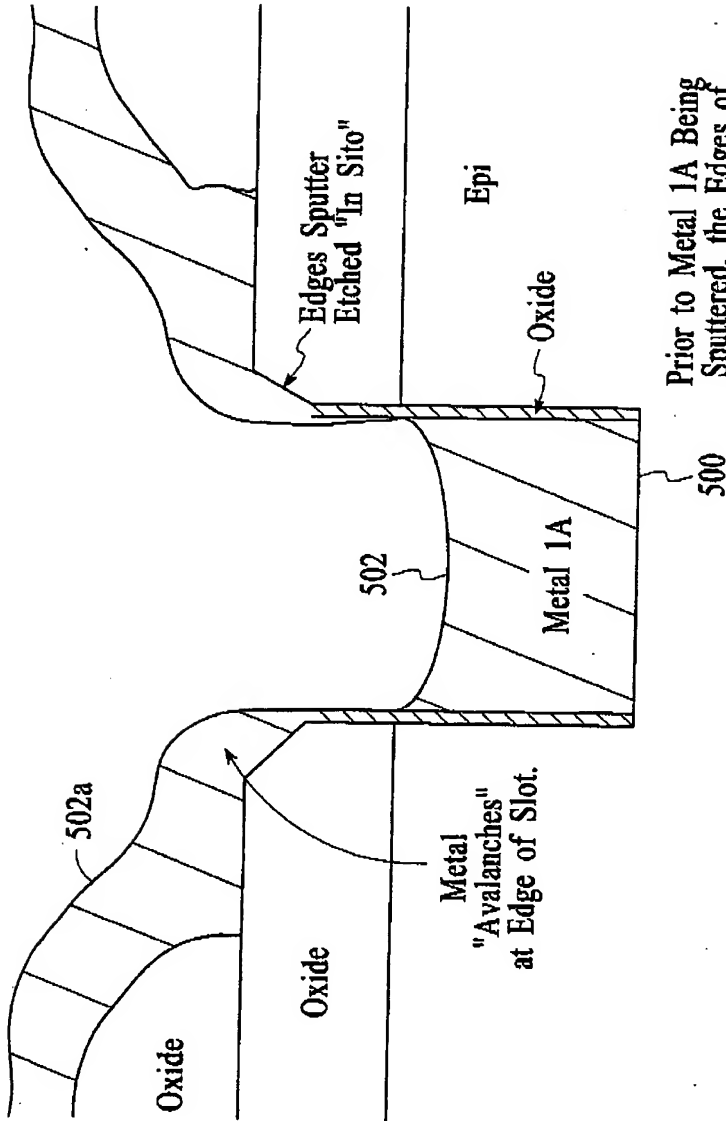
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Double Slot for  
Double Width of Metal  
3  $\mu\text{m}$  Space Between Slots

FIG. 4A

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Prior to Metal 1A Being Sputtered, the Edges of the Oxides are Sputtered Etched "In Situ" and 1A Deposited

FIG. 5

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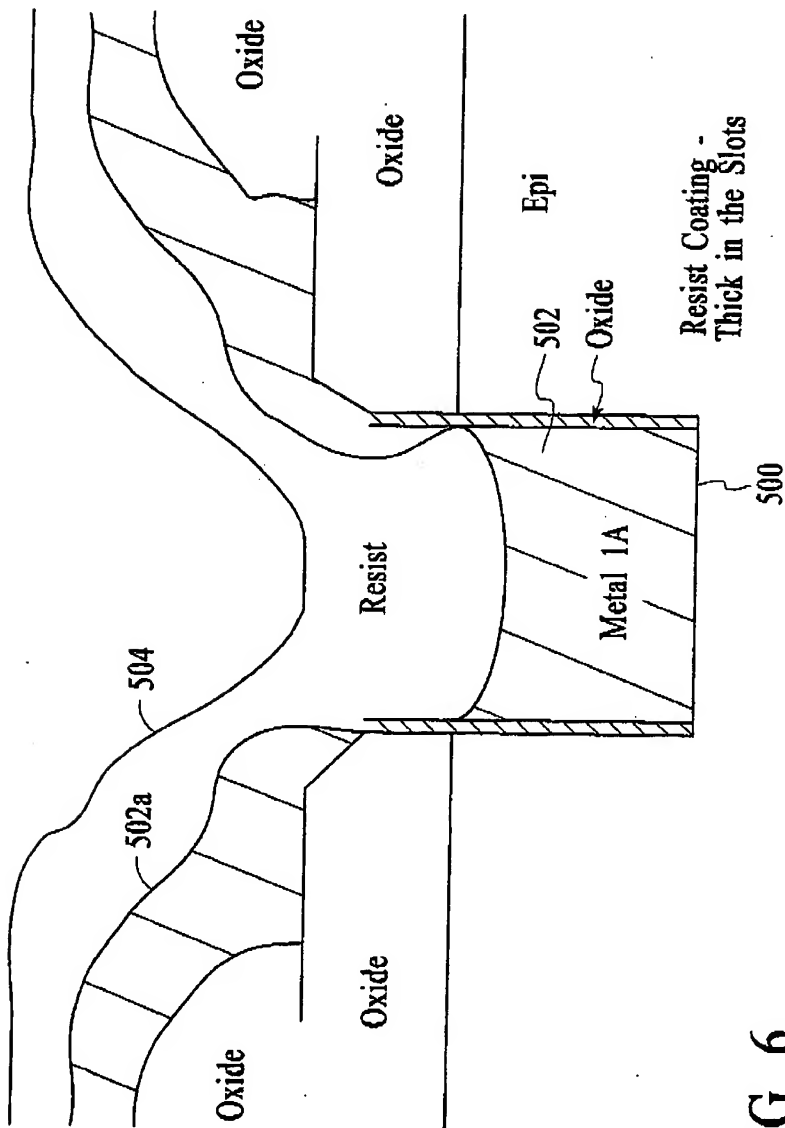
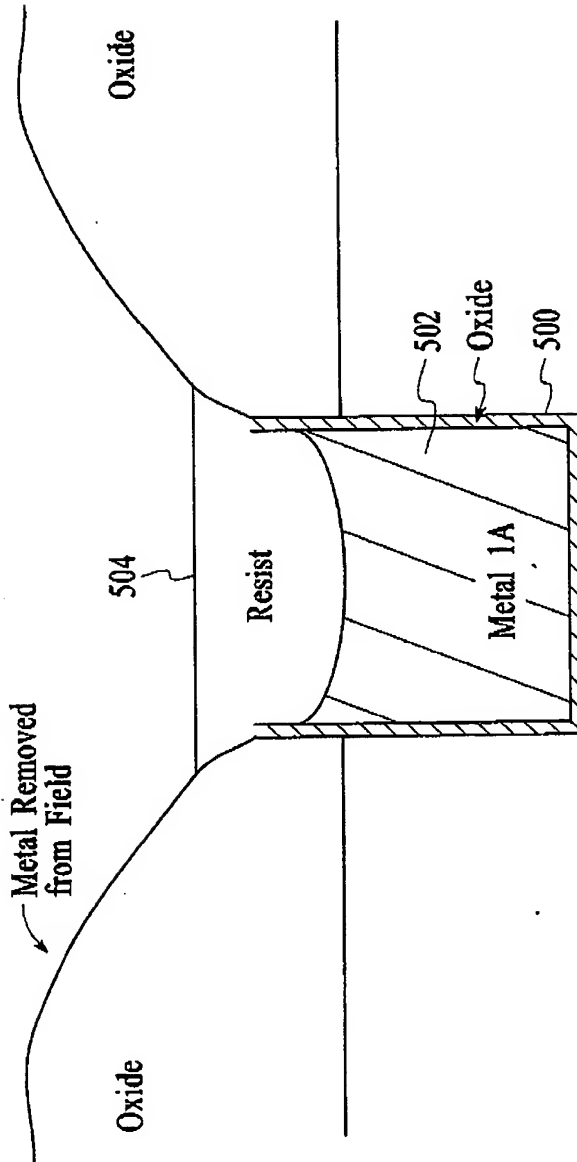


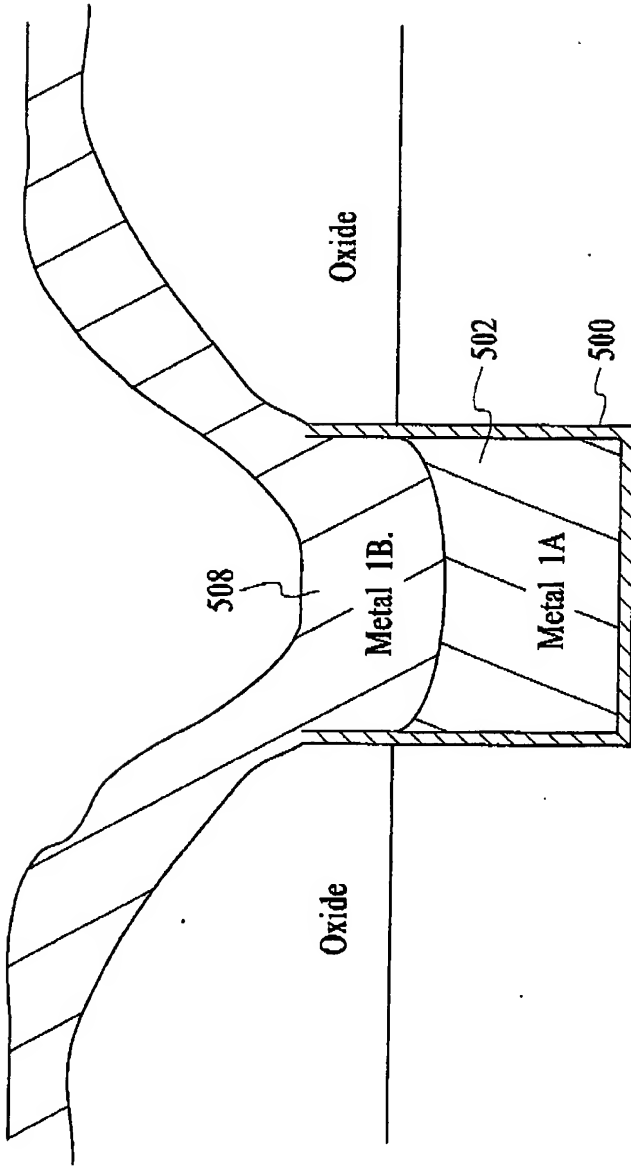
FIG. 6



**Resist Planar Etched Leaving Resist in Slots. Field Metal Etched Off.**

FIG. 7

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Resist Stripped & Second Metal 1B  
Sputter Deposited

FIG. 8

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FIG. 9

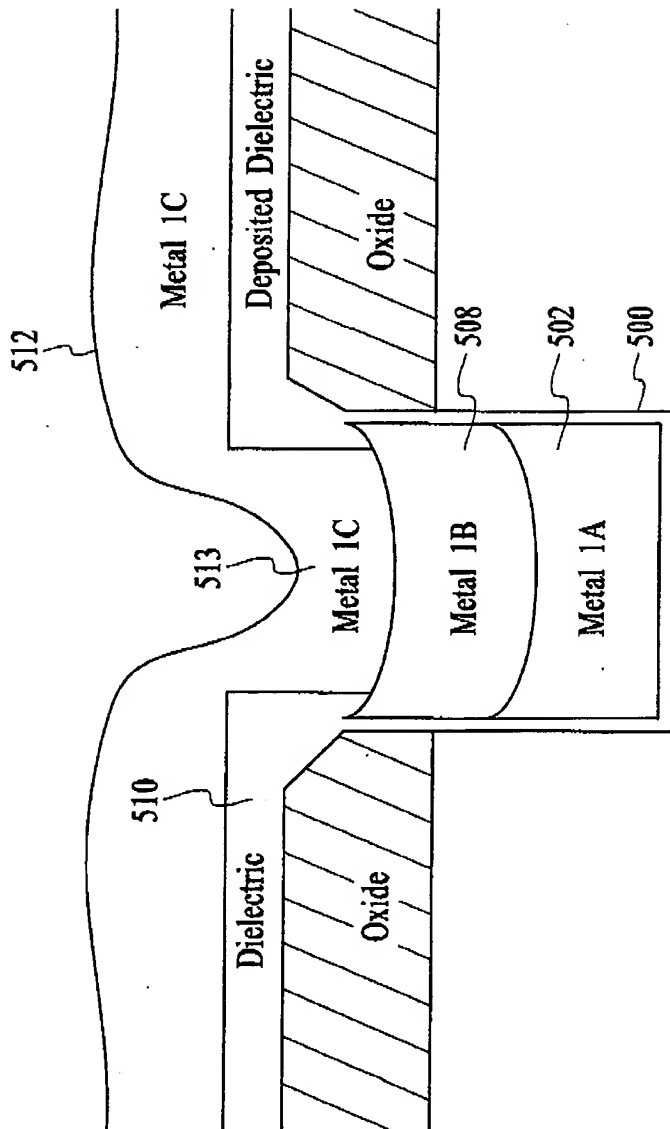
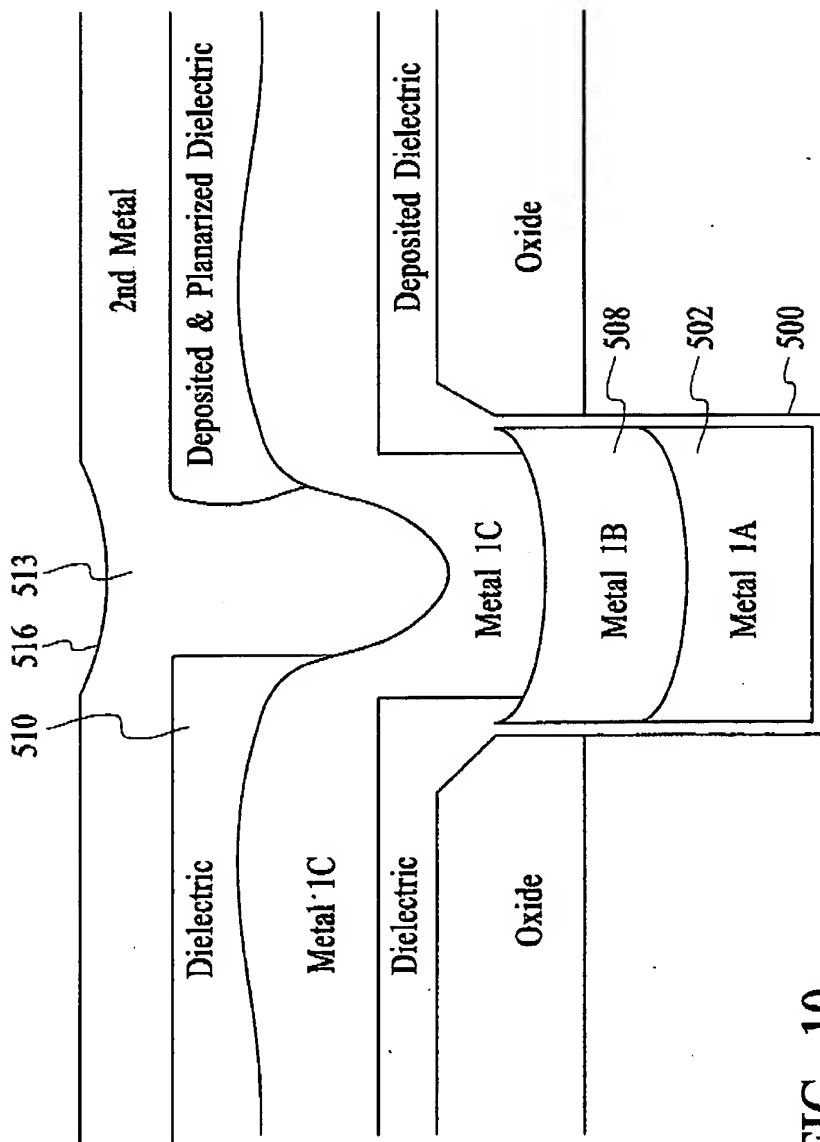


FIG. 9

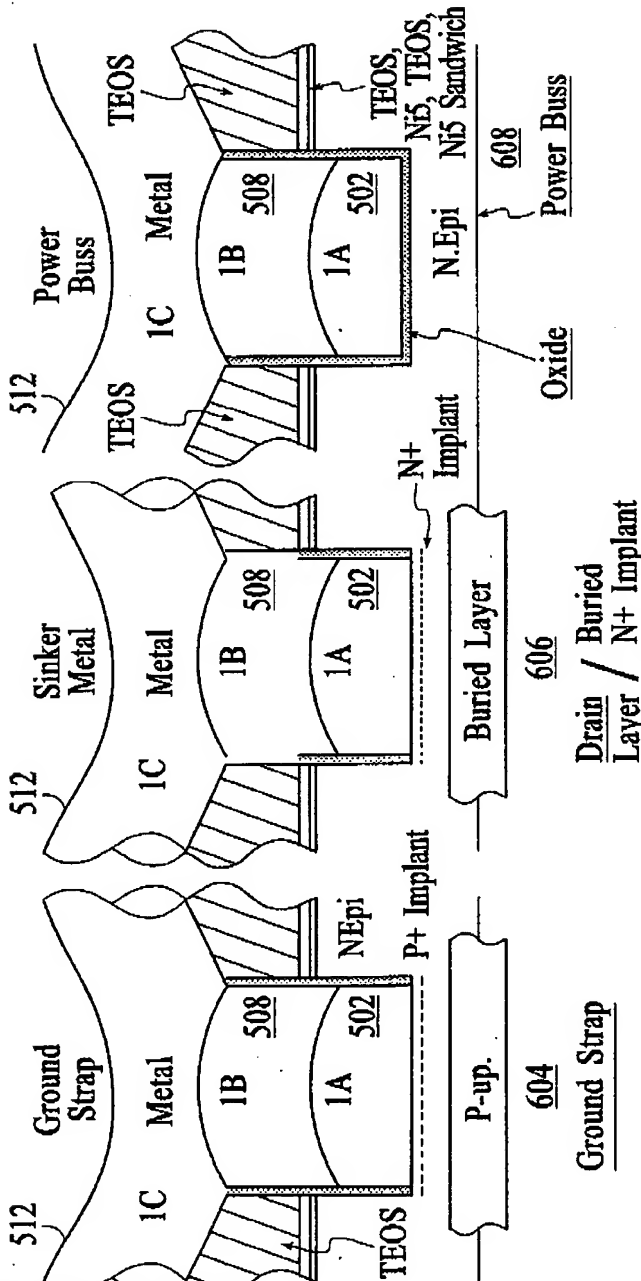


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**FIG. 10**

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Ground Strap / Power Buss / Drain Metal Sinker

Shown after layers of Dielectric followed by 90 OD A TEOS - Polish - Slot Mask - Metal. Metal 1.5 - 2.0  $\mu\text{m}$  deposited.

Power Metal

FIG. 11

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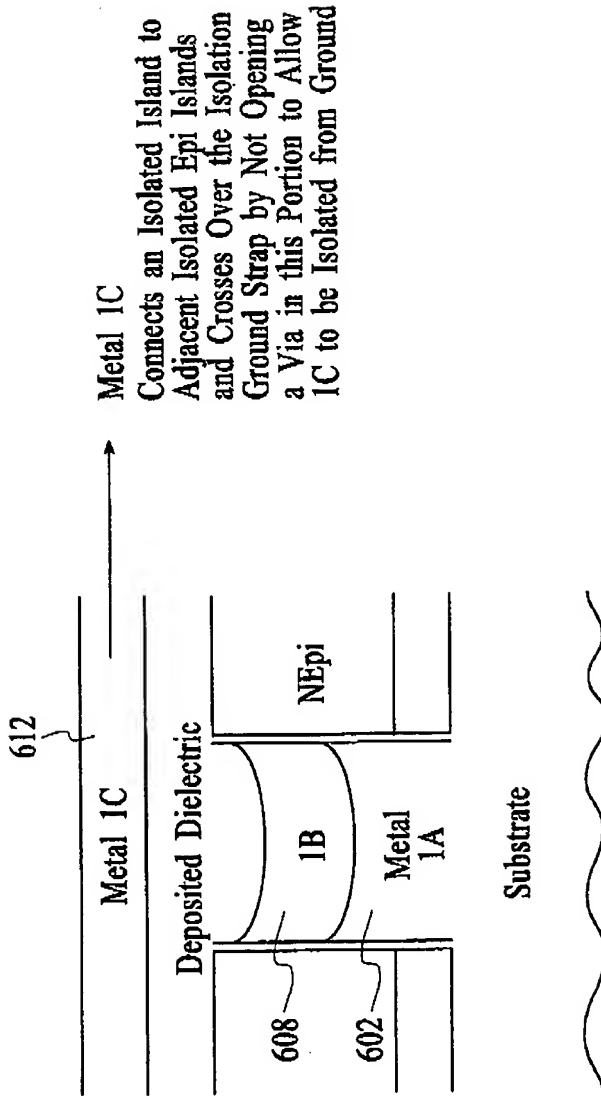


FIG. 12